*k*SA MOS *Ultra*-Scan

High Resolution Curvature and Stress Mapping System

Overview

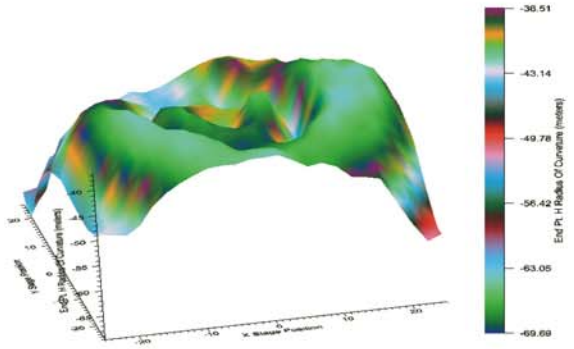
The kSA MOS *Ultra*-Scan is a flexible, high-resolution scanning curvature and stress measurement system. The *Ultra*-Scan maps the curvature of semiconductor wafers, optical mirrors, lenses, or practically any polished surface. Scans are fully programmable for selected area, line scan, or full area map. The system also provides quantitative film stress with full area map by first scanning the bare substrate and then re-scanning the sample post-process.

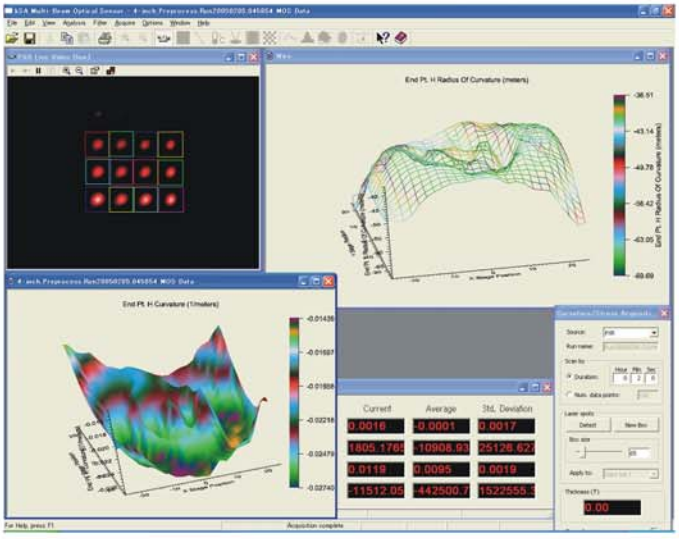
Applications

Map the curvature of any polished surface, including:

- Semiconductor wafers (Si, SOI, Compound Semi)
- Optical coatings (mirror, lenses, and glass)
- Thin-film stress measurement

Radius of Curvature Profile





Features

- Curvature and stress mapping at 2 um spatial resolution
- >50 km radius of curvature resolution
- Post-process stress determination
- Patented, 2-D array analysis
- 200 mm x,y scanning range
- Powerful, easy-to-use imaging and analysis software

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